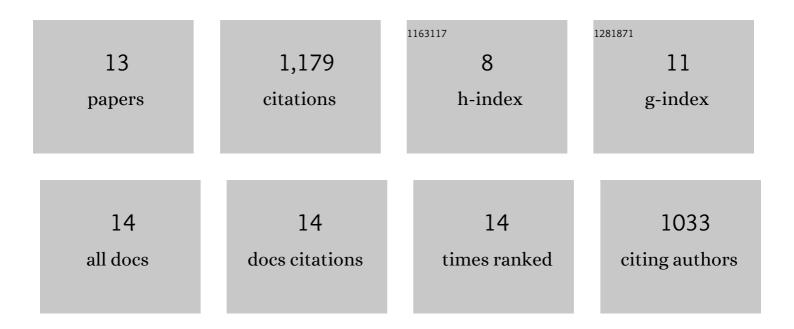
Martina Lattemann

List of Publications by Year in descending order

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| # | Article | IF | CITATIONS |
|----|--|------------------|---------------------|
| 1 | MD study of C diffusion in WC/W interfaces observed in cemented carbides. International Journal of Refractory Metals and Hard Materials, 2019, 85, 105054. | 3.8 | 6 |
| 2 | Magnetic Saturation: Understanding Quality Control of Hard Metals in Industry - A Quantum Mechanics Approach (Adv. Theory Simul. 6/2019). Advanced Theory and Simulations, 2019, 2, 1970021. | 2.8 | 0 |
| 3 | Influence of characteristic properties of PCD grades on the wear development in turning of β-titanium alloy (Ti5Al5V5Mo3Cr). Wear, 2019, 426-427, 1594-1602. | 3.1 | 15 |
| 4 | Understanding Quality Control of Hard Metals in Industry ―A Quantum Mechanics Approach. Advanced Theory and Simulations, 2019, 2, 1900035. | 2.8 | 2 |
| 5 | Quantum mechanics basis of quality control in hard metals. Acta Materialia, 2019, 169, 1-8. | 7.9 | 4 |
| 6 | High resolution STEM investigation of interface layers in cemented carbides. International Journal of Refractory Metals and Hard Materials, 2018, 72, 135-140. | 3.8 | 14 |
| 7 | Specific carbide substrate design to enhance tool performance in machining of Ti5553. Procedia CIRP, 2018, 77, 598-601. | 1.9 | 9 |
| 8 | A consistent path for phase determination based on transmission electron microscopy techniques and supporting simulations. Micron, 2018, 115, 41-49. | 2.2 | 0 |
| 9 | Electronic origin of structure and mechanical properties in Y and Nb alloyed Ti–Al–N thin films. International Journal of Materials Research, 2011, 102, 735-742. | 0.3 | 38 |
| 10 | Microstructure Evolution During Spark Plasma Sintering of Metastable (ZrO ₂ –3 mol%) Tj ETQq0 0 the American Ceramic Society, 2010, 93, 2864-2870. | 0 rgBT /C 3.8 | overlock 10 T 20 |
| 11 | Transition between the discharge regimes of high power impulse magnetron sputtering and conventional direct current magnetron sputtering. Plasma Sources Science and Technology, 2009, 18, 045008. | 3.1 | 79 |
| 12 | Cross-field ion transport during high power impulse magnetron sputtering. Plasma Sources Science and Technology, 2008, 17, 035021. | 3.1 | 106 |
| 13 | Ionized physical vapor deposition (IPVD): A review of technology and applications. Thin Solid Films, | 1.8 | 886 |